L Number	Hits	Search Text	DB	Time stamp
1	1532545	memory or floating adj gate	USPAT;	2004/09/16 14:37
2			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	60007		IBM_TDB	0004/00/40 44-00
2	62887	silicide or salicide or polycide or policide	USPAT;	2004/09/16 14:32
			US-PGPUB; EPO; JPO;	
			DERWENT;	
			IBM TDB	
3	2619892	source	USPAT;	2004/09/16 15:56
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
4	3375698	throughhole or through adj hole or viahole or via adj hole or via or	USPAT;	2004/09/16 14:34
		interconnect\$4 or inter adj connect\$4	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
_	400	pourse mond (throughbale authorise) and halo and delicate a	IBM_TDB	2004/00/40 44:44
5	166	source near4 (throughhole or through adj hole or viahole or via adj hole or via or interconnect\$4 or inter adj connect\$4) near4	USPAT;	2004/09/16 14:41
			US-PGPUB;	
Ì		(silicide or salicide or polycide or policide)	EPO; JPO; DERWENT;	
			IBM_TDB	
6	57	(memory or floating adj gate) and (source near4 (throughhole or	USPAT;	2004/09/16 14:35
٠	0,	through adj hole or viahole or via adj hole or via or interconnect\$4	US-PGPUB;	2004/00/10 14:00
		or inter adj connect\$4) near4 (silicide or salicide or polycide or	EPO; JPO;	
}		policide))	DERWENT;	
			IBM_TDB	
8	47		USPAT;	2004/09/16 14:37
		through adj hole or viahole or via adj hole or via or interconnect\$4	US-PGPUB;	
		or inter adj connect\$4) near4 (silicide or salicide or polycide or	EPO; JPO;	
		policide))) and (@ad < "20010111")	DERWENT;	ļ
_			IBM_TDB	0004/00/40 44 07
9	1532545	memory or floating adj gate	USPAT;	2004/09/16 14:37
			US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM_TDB	
10	47	(memory or floating adj gate) and (source near4 (throughhole or	USPAT;	2004/09/16 14:43
		through adj hole or viahole or via adj hole or via or interconnect\$4	US-PGPUB;	200 1700/10 11110
		or inter adj connect\$4) near4 (silicide or salicide or polycide or	EPO; JPO;	
		policide)) and (@ad < "20010111")	DERWENT;	
		, , , , ,	IBM_TDB	
11	7158	(over or upper or above or top or cap or capping) near2 (silicide	USPAT;	2004/09/16 14:41
		or salicide or polycide or policide)	US-PGPUB;	
			EPO; JPO;	1
			DERWENT;	
40	_	anne mand (Abanyahhala anthanyah adi) da anthanyah	IBM_TDB	0004/00/40 44 40
12	7	source near4 (throughhole or through adj hole or viahole or via	USPAT;	2004/09/16 14:42
		adj hole or via or interconnect\$4 or inter adj connect\$4) near4	US-PGPUB;	
		((over or upper or above or top or cap or capping) near2 (silicide or salicide or polycide or policide))	EPO; JPO; DERWENT;	
		or salicide or polycide or policide))	IBM_TDB	1
13	5	(memory or floating adj gate) and (source near4 (throughhole or	USPAT;	2004/09/16 15:05
		through adj hole or viahole or via adj hole or via or interconnect\$4	US-PGPUB;	2004/00/10 10:00
		or inter adj connect\$4) near4 ((over or upper or above or top or	EPO; JPO;	
		cap or capping) near2 (silicide or salicide or polycide or policide	DERWENT;	1
))) and (@ad < "20010111")	IBM_TDB	
14	41951	common near2 source	· USPAT;	2004/09/16 15:02
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	1
	1		IBM_TDB	

15	6	((over or upper or above or top or cap or capping) near2 (silicide	USPAT;	2004/09/16 15:05
1		or salicide or polycide or policide)) near4 (common near2 source)	US-PGPUB; EPO; JPO; DERWENT;	
			IBM TDB	
16	29	((over or upper or above or top or cap or capping) near2 (silicide	USPAT;	2004/09/16 15:05
		or salicide or polycide or policide)) same (common near2 source)	US-PGPUB;	2004/00/10 10:00
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
17	6	(((over or upper or above or top or cap or capping) near2 (silicide	USPAT;	2004/09/16 16:22
		or salicide or polycide or policide)) same (common near2	US-PGPUB;	
		source)) and (memory or floating adj gate) and (@ad < "20010111")	EPO; JPO; DERWENT;	
		20010111)	IBM TDB	
20	2	("5280446" "5656527").PN.	USPAT	2004/09/16 15:10
21	61421	self adj align\$4	USPAT;	2004/09/16 15:57
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	450007		IBM_TDB	0004/004/5 45 55
22	158394	inplant or implant or inplanting or implanting	USPAT;	2004/09/16 15:57
			US-PGPUB; EPO; JPO;	
			DERWENT:	
			IBM_TDB	
23	26866	ild or (interlevel or intermediate) near2 (dielectric or oxide or	USPAT;	2004/09/16 16:01
		insulat\$4)	US-PGPUB;	
1			EPO; JPO;	
			DERWENT;	
24	687259	planar\$4 or cmp or polish\$4	IBM_TDB USPAT;	2004/09/16 16:01
24	001239	planary4 of chip of polishy4	US-PGPUB;	2004/09/10 10:01
			EPO; JPO;	
1			DERWENT;	
			IBM_TDB	
25	6015	(silicide or salicide or polycide or policide) near2 gate	USPAT;	2004/09/16 16:01
			US-PGPUB; EPO; JPO;	
1			DERWENT:	
			IBM_TDB	
26	2387	(self adj align\$4) near4 (inplant or implant or inplanting or	USPAT;	2004/09/16 16:02
		implanting)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
27	1	((self adj align\$4) near4 (inplant or implant or inplanting or	IBM_TDB USPAT;	2004/09/16 16:21
	•	implanting)) and (ild or (interlevel or intermediate) near2	US-PGPUB;	200-700/10 10.21
		(dielectric or oxide or insulat\$4)) same (planar\$4 or cmp or	EPO; JPO;	
		polish\$4) same ((silicide or salicide or polycide or policide) near2	DERWENT;	
	<u>.</u>	gate)	IBM_TDB	
28	21	(ild or (interlevel or intermediate) near2 (dielectric or oxide or	USPAT;	2004/09/16 16:25
		insulat\$4)) same (planar\$4 or cmp or polish\$4) same ((silicide or salicide or polycide or policide) near2 gate)	US-PGPUB; EPO; JPO;	
		Sandre of polydide of polidide / fieal2 gate)	DERWENT;	
			IBM_TDB	
29	13	((ild or (interlevel or intermediate) near2 (dielectric or oxide or	USPAT;	2004/09/16 16:28
		insulat\$4)) same (planar\$4 or cmp or polish\$4) same ((silicide or	US-PGPUB;	
		salicide or polycide or policide) near2 gate)) and (@ad <	EPO; JPO;	
		"20010111")	DERWENT;	
30	. 23	(planar\$4 or cmp or polish\$4) near4 (expos\$4 or open\$4 or top)	IBM_TDB USPAT;	2004/09/16 16:33
55	. 23	near4 gate same ((silicide or salicide or polycide or policide)	US-PGPUB;	2007/03/10 10.33
		near2 gate)	EPO; JPO;	
		•	DERWENT;	
			IBM_TDB	

	r			
31	12	((planar\$4 or cmp or polish\$4) near4 (expos\$4 or open\$4 or top) near4 gate same ((silicide or salicide or polycide or policide) near2 gate)) and (@ad < "20010111")	USPAT; US-PGPUB; EPO; JPO;	2004/09/16 16:33
		,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	DERWENT;	
			IBM_TDB	
32	12		USPAT;	2004/09/16 16:28
		near4 gate same ((silicide or salicide or polycide or policide) near2 gate)) and (@ad < "20010111")) not (((ild or (interlevel or	US-PGPUB; EPO; JPO;	
		intermediate) near2 (dielectric or oxide or insulat\$4)) same	DERWENT;	
		(planar\$4 or cmp or polish\$4) same ((silicide or salicide or	IBM_TDB	
		polycide or policide) near2 gate)) and (@ad < "20010111"))	_	
33	362		USPAT;	2004/09/16 16:34
		polycide or policide) near2 gate)	US-PGPUB;	
i			EPO; JPO;	
			DERWENT; IBM_TDB	
34	228	((planar\$4 or cmp or polish\$4) same ((silicide or salicide or	USPAT;	2004/09/16 16:34
.		polycide or policide) near2 gate)) and (@ad < "20010111")	US-PGPUB:	2004/03/10 10:04
		, , , , , , , , , , , , , , , , , , ,	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
35	59	(planar\$4 or cmp or polish\$4) near8 ((silicide or salicide or	USPAT;	2004/09/16 16:34
		polycide or policide) near2 gate)	US-PGPUB;	
			EPO; JPO; DERWENT:	
			IBM TDB	
36	39	((planar\$4 or cmp or polish\$4) near8 ((silicide or salicide or	USPAT;	2004/09/16 17:00
		polycide or policide) near2 gate)) and (@ad < "20010111")	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
37	2	 5869396.pn.	IBM_TDB USPAT;	2004/09/16 17:01
31	2	5009590.pm.	US-PGPUB;	2004/09/16 17:01
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
38	2	5869396.pn. and (planar\$4 or cmp or polish\$4)	USPAT;	2004/09/16 17:01
			US-PGPUB;	
			EPO; JPO;	
			DERWENT; IBM TDB	
39	3043	((438/626) or (438/647) or (438/645) or (438/649) or	USPAT;	2004/09/16 17:23
		(438/257)).CCLS.	US-PGPUB;	
		, , , , , , , , , , , , , , , , , , , ,	EPO; JPO;	
	ļ		DERWENT;	
		0700770	IBM_TDB	0004/004/004
-	1 1	6720579.pn. 6376876.pn.	USPAT USPAT	2004/09/16 13:12
	L	0310010.pm.	USFAI	2004/09/16 15:56